# **WEST Search History**

Hide Items ... Restore Clear Cancel

DATE: Thursday, January 05, 2006

Hide?	<u>Set</u> Name	Query	<u>Hit</u> Count			
DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ						
	L15	113 and 15	5			
	L14	L13 same (substrate or semiconductor or workpiece or wafer)	19			
<u></u>	L13	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet or passage or hollow) with (rotat\$3 or spin\$5)) same ((wall or portion or top) with (gradient or inclin\$5 or angle))	821			
	DB =	EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ				
Γ.	L12	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet or passage or hollow) with (rotat\$3 or spin\$5)) same ((wall or portion or top) with (gradient or inclin\$5 or angle))	17			
C	L11	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet or passage or hollow) with (rotat\$3 or spin\$5)) same (wall with (gradient or inclin\$5 or angle))	8			
Ŀ	L10	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet or passage or hollow) with (air adj5 suck\$5) with (rotat\$3 or spin\$5)) same (wall with (gradient or inclin\$5 or angle))	3 0			
	DB =	PGPB,USPT,USOC; PLUR=YES; OP=ADJ				
□	L9	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet or passage or hollow) with (air adj5 suck\$5) with (rotat\$3 or spin\$5)) same (wall with (gradient or inclin\$5 or angle))	3 1			
	DB =	USPT,USOC; PLUR=YES; OP=ADJ				
C	L8	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet or passage or hollow) with air with (rotat\$3 or spin\$5)) same (wall with (gradient or inclin\$5 or angle))	59			
	L7	L6 and 15	2			
L.	L6	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet or passage or hollow) with (rotat\$3 or spin\$5)) same (wall with (gradient or inclin\$5 or angle))	352			
<u> </u>	L5	156/345.11,345.23,345.51;134/94.1,184,902;15/300.1,302,303,320,345,383.ccls.	5748			
⊏	L4	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet) with (rotat\$3 or spin\$5)) same (wall with (gradient or inclin\$5 or angle))	195			
	DB =	PGPB; PLUR=YES; OP=ADJ				
Ľ	L3	(apparatus or chamber or tank) same (hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet) with (rotat\$3 or spin\$5)) same (wall with (gradient or inclin\$5 or angle))	8			
		(hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet) with (rotat\$3 or				

	L2	spin\$5)) same (wall with (gradient or inclin\$5 or angle))	20
Γ.	L1	(hold\$3 or support\$3 or chuck\$3) same (plate with (hole or inlet) with (rotat\$3 or spin\$5)) same wall same (gradient or inclin\$5 or angle)	45

#### END OF SEARCH HISTORY

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	DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ					
Ľ	L18	L17 and ((Apparatus or chamber or tank) same (plate with (hole or passage or hollow or tub\$3 or pip\$3) with (rotat\$4 or spin\$4)) same (gradient or inclin\$5 or angle))	3			
Γ.	L17	L16 or l15 or l13 or l11	1843			
Γ.,	L16	okamura-katsuya\$.in.	95			
匚	L15	ema-tatsuhiko\$.in.	38			
Γ	L14	ema-tasuhiko\$.in.	0			
Γ.	L13	takahashi-riichiro\$.in.	23			
	L12	takanashi-riichiro\$.in.	0			
<u> </u>	L11	ito-shinichi\$.in.	1752			
	L10	L9 and ((Apparatus or chamber or tank) same (plate with (hole or passage or hollow or tub\$3 or pip\$3) with (rotat\$4 or spin\$4)) same (gradient or inclin\$5 or angle))	5			
Γ	L9	(kabushiki kaisha toshiba).as.	25712			
	DB=E	SPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ				
Γ.	L8	L7 same ((wall or top or portion) with (inclin\$5 or gradient or angle))	0			
Г	L7	(Apparatus or chamber or tank) same (semiconductor or wafer or substrate or workpiece)same (plate with (hole or passage or hollow or tub\$3 or pip\$3) with (rotat\$4 or spin\$4))	141			
	L6	L4 same ((wall or top or portion) with (inclin\$5 or gradient or angle))	0			
DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ						
	L5	L4 same ((wall or top or portion) with (inclin\$5 or gradient or angle))	34			
	L4	L3 same (hold\$3 or support\$3 or chuck\$3)	397			
Г	L3	(Apparatus or chamber or tank) same (semiconductor or wafer or substrate or workpiece)same (plate with (hole or passage or hollow or tub\$3 or pip\$3) with (rotat\$4 or spin\$4))	565			
DB=USPT; PLUR=YES; OP=ADJ						
Γ.	L2	6265323.pn. or 6372413.pn. or 6528128.pn. or 6550990.pn. or 6579382.pn.	5			
Ī	L1	6006763.pn.	1			

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	DB=P	PGPB, USPT, USOC, EPAB, JPAB, DWPI; PLUR=YES; OP=ADJ				
C	L19	6881058.pn. or 6059880.pn. or 6231917.pn. or 6372285.pn. or 6372413.pn. or 6550990.pn.	11			
⊏	L18	L17 and ((Apparatus or chamber or tank) same (plate with (hole or passage or hollow or tub\$3 or pip\$3) with (rotat\$4 or spin\$4)) same (gradient or inclin\$5 or angle))	3			
Γ.	L17	L16 or l15 or l13 or l11	1843			
Γ	L16	okamura-katsuya\$.in.	95			
	L15	ema-tatsuhiko\$.in.	38			
	L14	ema-tasuhiko\$.in.	0			
	L13	takahashi-riichiro\$.in.	23			
С	L12	takanashi-riichiro\$.in.	0			
	L11	ito-shinichi\$.in.	1752			
<u></u>	L10	L9 and ((Apparatus or chamber or tank) same (plate with (hole or passage or hollow or tub\$3 or pip\$3) with (rotat\$4 or spin\$4)) same (gradient or inclin\$5 or angle))	5			
Γ.	L9	(kabushiki kaisha toshiba).as.	25712			
	DB=E	PAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ				
ΓΞ	L8	L7 same ((wall or top or portion) with (inclin\$5 or gradient or angle))	0			
П	L7	(Apparatus or chamber or tank) same (semiconductor or wafer or substrate or workpiece)same (plate with (hole or passage or hollow or tub\$3 or pip\$3) with (rotat\$4 or spin\$4))	141			
	L6	L4 same ((wall or top or portion) with (inclin\$5 or gradient or angle))	0			
	DB=P	PGPB,USPT,USOC; PLUR=YES; OP=ADJ				
	L5	L4 same ((wall or top or portion) with (inclin\$5 or gradient or angle))	34			
Γ.	L4	L3 same (hold\$3 or support\$3 or chuck\$3)	397			
⊏	L3	(Apparatus or chamber or tank) same (semiconductor or wafer or substrate or workpiece)same (plate with (hole or passage or hollow or tub\$3 or pip\$3) with (rotat\$4 or spin\$4))	565			
	DB=USPT; $PLUR=YES$ ; $OP=ADJ$					
Γ	L2	6265323.pn. or 6372413.pn. or 6528128.pn. or 6550990.pn. or 6579382.pn.	5			
	L1	6006763.pn.	1			

#### **END OF SEARCH HISTORY**